Air Force Institute of Technology



"Optimization of Carbon Nanotube Field Emission Arrays"

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Overview



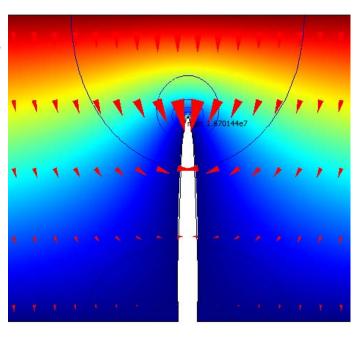
- Motivation
- CNT Array Models
- Simulation Results
- Conclusions



Motivation



- Carbon nanotubes as emitters
 - Narrow diameters
 - High aspect ratios
 - Good conductivity
 - High temperature stability
 - Structural strength



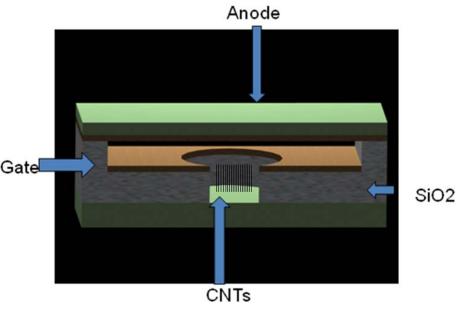
 CNT emission is due to high localized electric field that forms at small diameter tips.



Motivation



- Triode (gated) Devices
 - Lower extraction voltage
 - Simpler control
 - Reduce screening effects

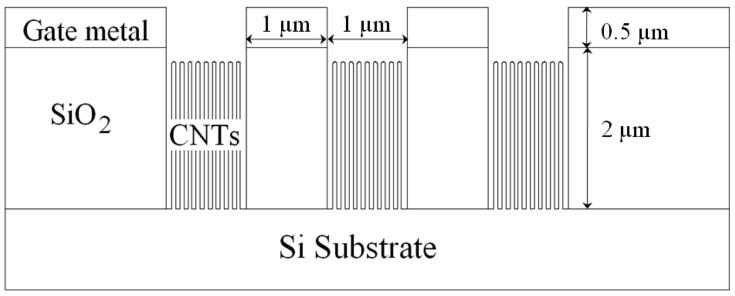


 Maximize field emission by optimizing array geometries within available fabrication processes to maximize the electric field strength at the CNT emitters.



CNT Array Models





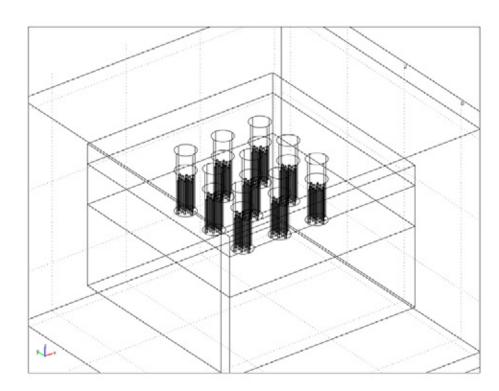
- 2-D model of base CNT array
 - CNTs with 50 nm diameter and 50 nm spacing
 - Array pitch of 1 µm
 - Array elements of 1 µm
 - Element shape (square and round)
 - Dielectric thickness of 2 µm



CNT Array Models



- Optimized electric field strength by varying:
 - CNT spacing
 - Array pitch
 - Array element dimensions
 - Element shape
 - Dielectric thickness
- Simulations used both
 2D and 3D models

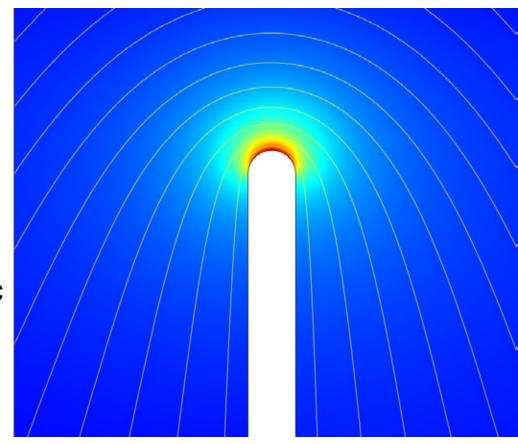






- CNT spacing within array element
 - Single CNT
 - 200 nm
 - 50 nm

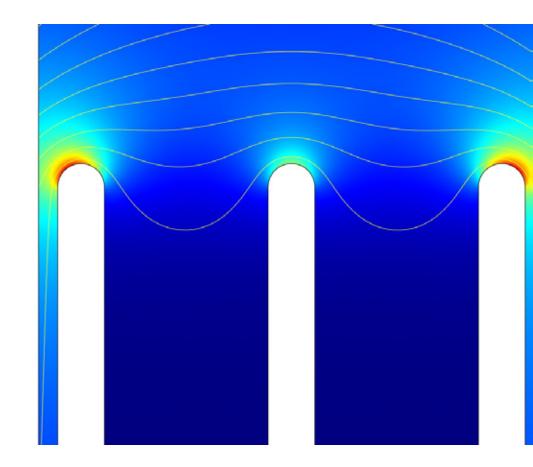
- Single CNT
 - Strongest E-field
 - Complete electrostatic field penetration







- 200 nm CNT separation
 - 3 CNTs
 - Significantly reduced penetration
 - 42% Reduction in center CNT E-field

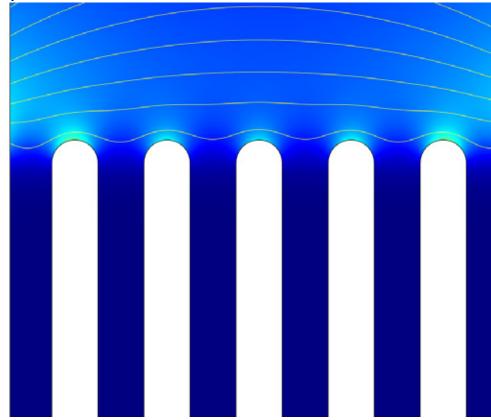






- 50 nm CNT separation
 - 9 CNTs (center 5 shown)
 - Significantly reduced penetration
 - 60% Reduction in center CNT E-field

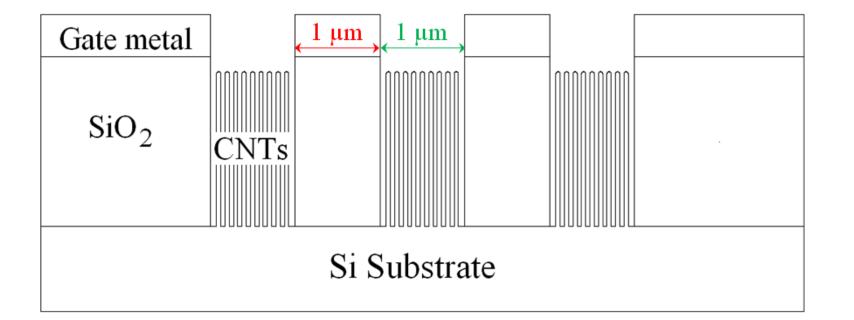
 Screening effects are significant within array elements





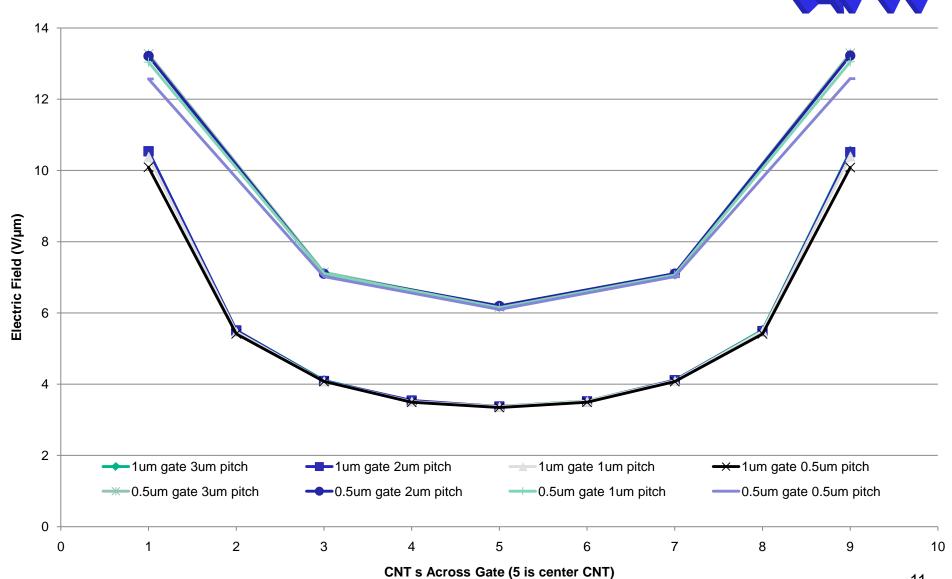


- Element pitch and dimension
 - Potential increase in field emission current density through increase in total number of elements with stronger E-fields
 - Element dimensions (green) of 1 μm and 0.5 μm simulated with pitches (red) of 3 μm, 2 μm, 1 μm, and 0.5 μm











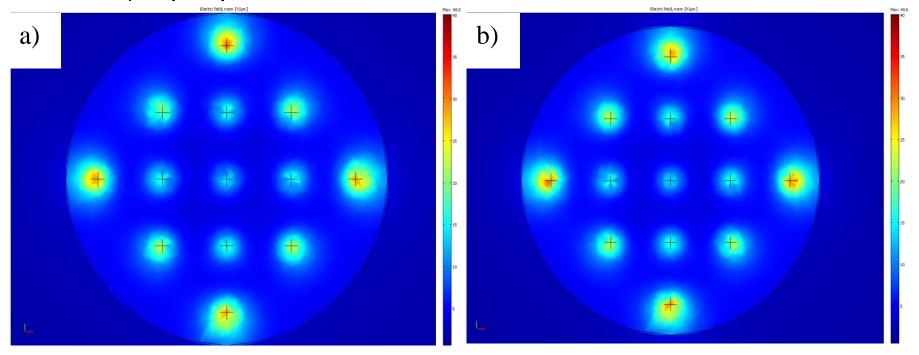


- Decreasing element dimensions increases E-field
 - Reduction from 1 μm to 0.5 μm increased E-field at center from 3.3 V/μm to 6.1 V/μm
- Pitch has little effect on E-field strength
 - Decreasing pitch from 3 µm to 0.5 µm had no effect on the E-field at the center of the element
 - ~4% drop at edge CNTs
 - Screening effects dominate center of elements





- 3D simulations also showed no difference between
 - a) 0.5 µm pitch
 - b) 1 µm pitch

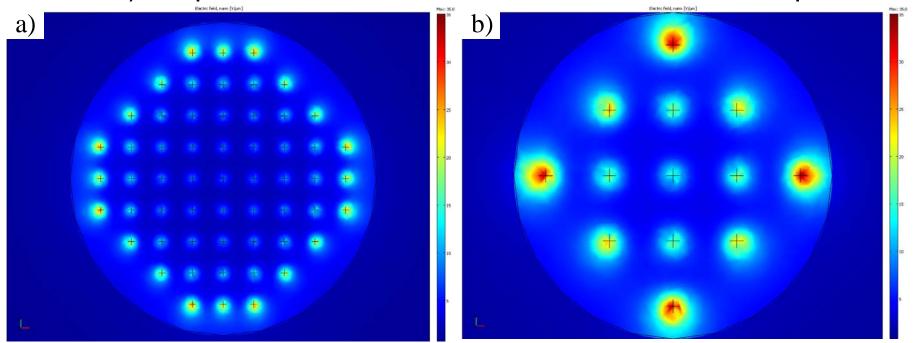


E-field strength at CNT tips across center element of a 3x3 array





- 3D simulations resulted in a greater increase in Efield with a reduction in element dimension
 - a) 1 μm element diameter: E-field at center 5.3 V/μm
 - b) 0.5 μm element diameter: E-field at center 14.7 V/μm

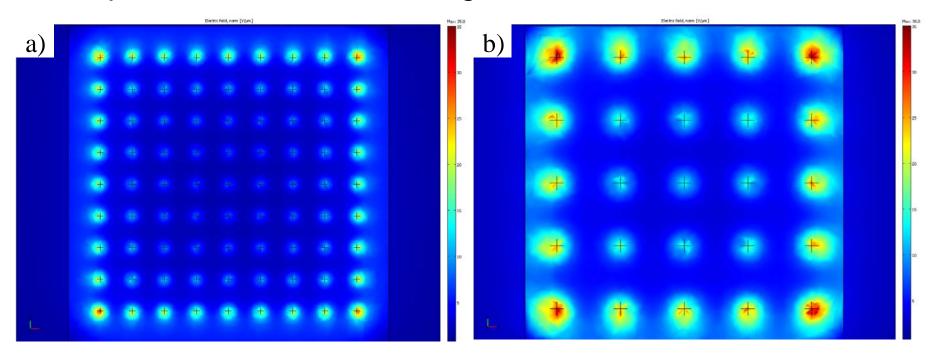


E-field strength at CNT tips across center element of a 3x3 array





- Square elements also showed greater increase in E-field
 - a) 1 μm element: E-field at center 7.8 V/μm
 - b) 0.5 μm element: E-field at center 17.7 V/μm
- Square elements had stronger E-field at element center

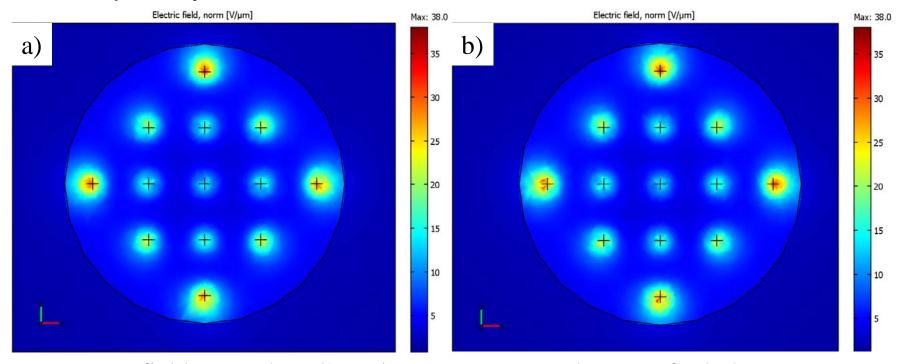


E-field strength at CNT tips across center element of a 3x3 array





- Reduction in dielectric layer had little effect on the E-field
 - a) 1 μm dielectric layer: E-field at center 14.7 V/μm
 - b) 2 μm dielectric layer: E-field at center 15.2 V/μm
- 0.5 µm layer resulted in a 10% reduction of center E-field



E-field strength at CNT tips across center element of a 3x3 array



Conclusions



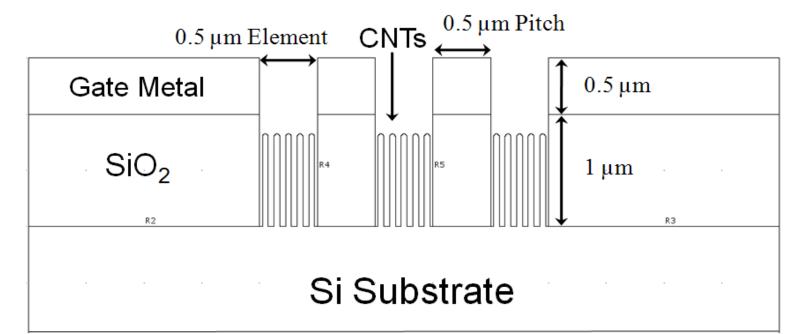
- Electrostatic screening between CNTs dominates the E-field strength within an element
- Pitch can be reduced to increase array current densities
- Smaller element dimensions significantly increases the E-field magnitude across an element
 - Also increases the total number of elements in the array
- Square elements had stronger E-field at the center of the element
- Large reductions in dielectric thickness resulted in only small decreases in E-field magnitude



Conclusions



- Optimized CNT field emission array design based on available fabrication capabilities
 - Circular elements with 0.5 µm diameter
 - 0.5 µm pitch
 - 1 µm thick dielectric layer







Questions

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